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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
(Case No. 213.002-D1-US)

In the Application of: **Ye et al.**

Serial No: **10/646,313**

Filed: **August 22, 2003**

Title: **System and Method for Lithography
Process Monitoring and Control**

) Group Art Unit: **2878**

) Before Examiner: **Que Tan Le**

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Certificate of Mailing under 37 CFR 1.8

I hereby certify that the attached Statement of Related Applications (1 page) is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to:

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on May 17, 2004.

Michiko Sites

Signature

Michiko Sites

Print Name of Person Signing Certificate



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STATEMENT OF RELATED APPLICATIONS

Dear Sir:

The above-referenced application is related to the following applications which all claim priority to "System and Method for Lithography Process Monitoring and Control", Serial No. 10/390,806, filed March 18, 2003:

1. "System and Method for Lithography Process Monitoring and Control", Serial No. 10/703,732, filed November 7, 2003 (still pending); and
2. "System and Method for Lithography Process Monitoring and Control", Serial No. 10/755,809, filed January 12, 2004 (still pending).

Date: May 17, 2004

Respectfully submitted,

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